

## UNITED STATES DESCRIPTION OF COMMERCE

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FIRST NAMED INVENTOR ATTORNEY DOCKET NO. APPLICATION NO. **FILING DATE** 12/16/98 TAKASU H 09/212.915 A28838-I-A **EXAMINER** MM92/0830 BAKER & BOTTS ESTRADA, M 30 ROCKEFELLER PLAZA ART UNIT PAPER NUMBER NEW YORK NY 10112 2823 DATE MAILED: 08/30/00

Please find below and/or attached an Office communication concerning this application or proceeding.

**Commissioner of Patents and Trademarks** 

## Office Action Summary

Application No. 09/212,915

Applicant(s)

Examiner

Michelle Estrada

Group Art Unit 2823

Takasu



Responsive to communication(s) filed on	
☐ This action is <b>FINAL</b> .	
<ul> <li>Since this application is in condition for allowance except for in accordance with the practice under Ex parte Quayle, 1935</li> </ul>	
A shortened statutory period for response to this action is set to is longer, from the mailing date of this communication. Failure application to become abandoned. (35 U.S.C. § 133). Extension 37 CFR 1.136(a).	to respond within the period for response will cause the
Disposition of Claims	
X Claim(s) 1-9	is/are pending in the application.
Of the above, claim(s)	is/are withdrawn from consideration.
Claim(s)	is/are allowed.
	is/are rejected.
Claim(s)	
☐ Claims	
Application Papers    See the attached Notice of Draftsperson's Patent Drawing     The drawing(s) filed on	ted to by the Examiner.  is approved disapproved.  under 35 U.S.C. § 119(a)-(d).  f the priority documents have been  her)  International Bureau (PCT Rule 17.2(a)).
Acknowledgement is made of a claim for domestic priorit	y under 35 U.S.C. § 119(e).
Attachment(s)  Notice of References Cited, PTO-892  Information Disclosure Statement(s), PTO-1449, Paper No.  Interview Summary, PTO-413  Notice of Draftsperson's Patent Drawing Review, PTO-94  Notice of Informal Patent Application, PTO-152	<del></del> -
SEE OFFICE ACTION ON T	THE FOLLOWING PAGES

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Claims 1-9 are objected to because of the following informalities: In claim 1, line 3, it appears that --is-- should follow "layer". Appropriate correction is required.

Claim 2 is rejected under 35 U.S.C. 101 because the disclosed invention is inoperative and therefore lacks utility. The ion implanted region inherently "reaches for the surface" at the commencement of the annealing and diffusing step. Also, due to the gaussian distribution of implanted ions some ions reside at the surface of the substrate prior to the annealing and diffusing step.

It is noted that claim 6 is not accorded the benefit of the filing date of serial number 09/026096 under 35 U.S.C. 120 because support for claim 6 is not found therein.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 1 and 3-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over the combination of Yoshida et al and the following comments.

Yoshida et al discloses forming oxide layer 2 covering a substrate 1, implanting an impurity ion into region 5 where a buried region is to be formed, providing the substrate into a reactor furnace (col.3, line 36), preparing a non-oxidizing N<sub>2</sub> atmosphere (col.3, line 38) for annealing the substrate to activate and diffuse the implanted impurity by increasing to a first temperature (col.3, line 38), introducing cleaning gas into the reactor (col.3, lines 65+) followed by epitaxial growth on a surface of the wafer (col.4, lines 4+). Yoshida et al does not disclose performing the annealing/activation step and the epitaxial growth step in the same reactor, the relative temperatures of the step and the epitaxial growth step and the use of H<sub>2</sub> or HCl as the cleaning gas.

The examiner takes judicial notice that performing multiple processes in a single reactor to avoid contamination of the wafer by exposure to the atmosphere during transfer was known at the time of applicant's invention. It would have been within the scope of one of ordinary skill in the art to employ the known process for its known intended purpose to achieve the process steps of Yoshida et al. It would not be necessary to cool the wafer to room temperature in performing such a process, because that would merely add complexity to the process. It is noted that the claims do not require a continuous raising or lowering of the temperature to achieve the epitaxial growth temperature in recitation of "shifting the inside temperature of the reactor".

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The choice of particular temperatures for the annealing/activation and epitaxial growth steps would have been within a matter of routine optimization because temperatures for the steps are recognized as result effective variables.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Any inquiry of a general nature or relating to the status of this application should be directed to the Group Receptionist whose telephone number is (703) 308-0956. **See MPEP 203.08**.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to examiner Michelle Estrada whose telephone number is (703) 308-0729. The examiner can normally be reached on Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (703) 308-4918. The fax number for this group is (703)308-7722(7724,3431 and 3432). MPEP 502.01 contains instructions regarding procedures used in submitting responses by facsimile transmission.

George Fourson
Primary Examiner
Art Unit 2823

MEstrada August 25, 2000